

METHOD FOR THE DEPOSITION OF A REACTION CHAMBER FOR  
THE DEPOSITION OF SILICON NITRIDE FILMS

Timmermans et al.

Appl. No.: Unknown

Atty Docket: ASMINT.055AUS

BTBAS nitride deposition runs after in-situ clean

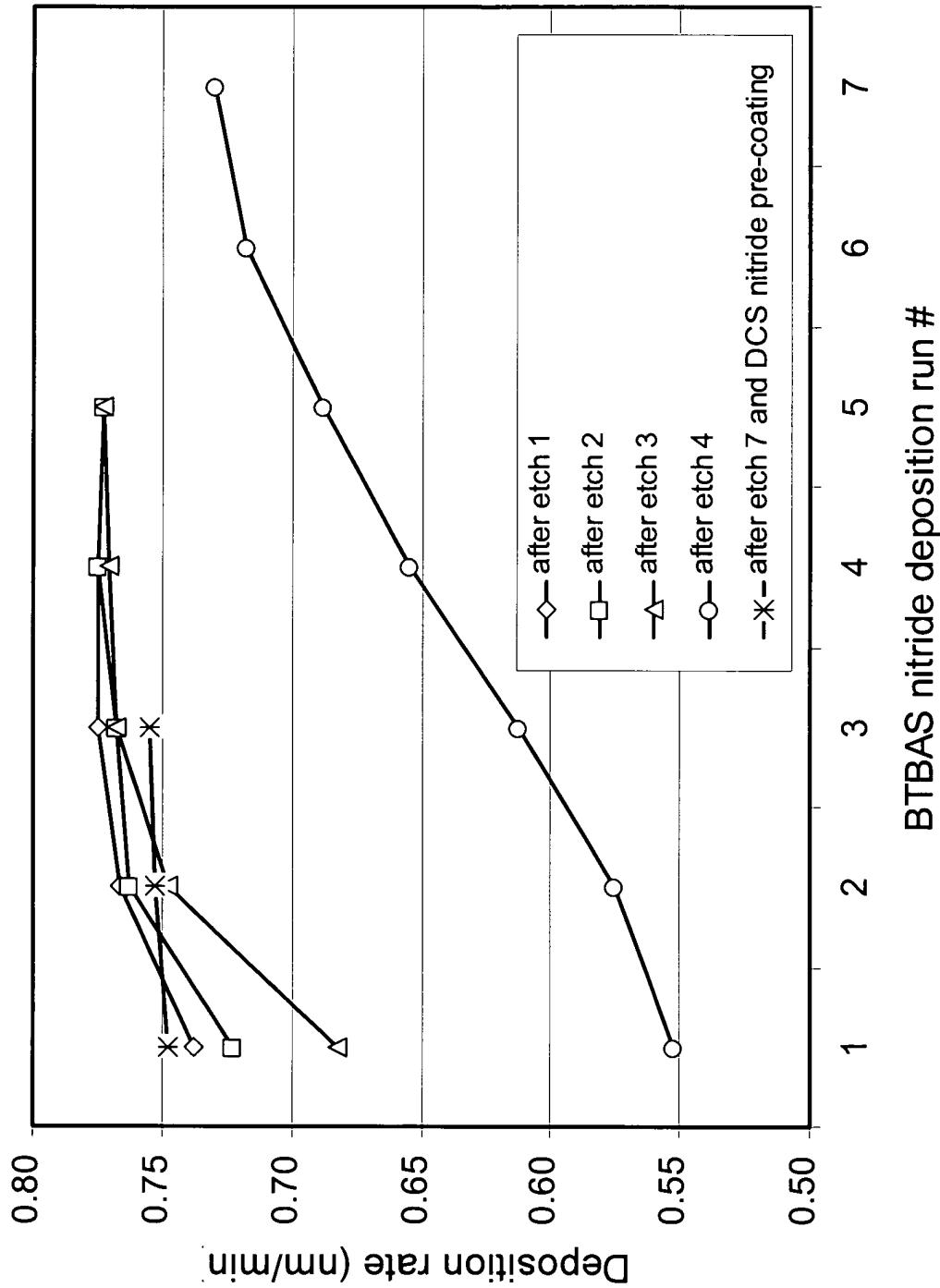


Figure 1